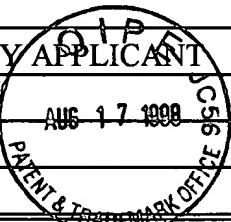


U.S. Department of Commerce, Patent and Trademark Office		Docket No.	Serial No.
		2735/PDC/JB	09/111,454
LIST OF RELEVANT ART CITED BY APPLICANT (Use several sheets if necessary)		Applicant	
		Ben-Porath et al	
		Filing Date	Group
		July 8, 1998	2723



## U.S. Patent Documents

*Examiner Initial		Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
AA							
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AH							
AI							
AJ							
AK							

## Foreign Patent Documents

## Translation

		Document Number	Date	Country	Class	Subclass	Yes	No
	AL							
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## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

VB	AR	"Electron Beam Pattern Inspection System Using Digital Image Processing"; Saitoh et al; J.Vac.Sci Technol B. Vol 4, No. 3 May/June 1986 - Pages 686-691
VB	AS	"Inspection For Defects of A Mask Containing One- to Submicrometer Patterns Using a Scanning Electron Microscope and Feature Extraction Method"; Y. Goto, et al; J.Vac. Sci. Technol 15 (3)0 May/June 1976; Pages 953-956
VB	AT	"Studies on an Electron-Beam Mask-defect Inspection System"; Y. Wada et al; J. Vac Sci Technol Vol 19 No. 1 May/June 1981

Examiner

*Khalil*

Date Considered

6/20/00

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

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SHEET 1 OF 1

# INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(PTO-1449)

ATTY. DOCKET NO.  
**49959-013**

SERIAL NO.  
09/111-454

**APPLICANT**  
**Ariel Ben-Porath**

FILING DATE  
July 8, 1998

GROUP  
~~2721~~ 2723

## **U.S. PATENT DOCUMENTS**

## **FOREIGN PATENT DOCUMENTS**

**OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)**

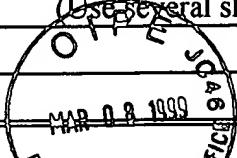
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	Porath, et al	
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*Examiner Initial	Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
VB	AA 5,862,055	1/19/99	Chen et al			RECEIVED
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AD						Group 2700
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## Foreign Patent Documents

## Translation

	Document Number	Date	Country	Class	Subclass	Yes	No
AL							
AM							
AN							
AO							
AP							

## OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

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